

## United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/716,765	11/19/2003	Sukesh Sandhu	303.596US2	6187
21186 75	590 10/02/2006		EXAMINER	
SCHWEGMA	N, LUNDBERG, WOE	NGUYEN, THANH T		
P.O. BOX 2938	3			
MINNEAPOLIS, MN 55402			ART UNIT	PAPER NUMBER
			2813	

Please find below and/or attached an Office communication concerning this application or proceeding.

## Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)		
10/716,765	SANDHU ET AL.		
Examiner	Art Unit		
Thanh T. Nguyen	2813		

	Thanh T. Nguyen	2813					
The MAILING DATE of this communication appe	ars on the cover sheet with the c	orrespondence add	ress				
THE REPLY FILED 31 August 2006 FAILS TO PLACE THIS AF	PPLICATION IN CONDITION FOR	ALLOWANCE.					
<ol> <li>The reply was filed after a final rejection, but prior to or on this application, applicant must timely file one of the follow places the application in condition for allowance; (2) a No a Request for Continued Examination (RCE) in compliance time periods:         <ol> <li>The period for reply expiresmonths from the mailing b)</li> <li>The period for reply expires on: (1) the mailing date of this A no event, however, will the statutory period for reply expire laws.</li> </ol> </li> </ol>	ving replies: (1) an amendment, aff tice of Appeal (with appeal fee) in ce with 37 CFR 1.114. The reply mug date of the final rejection.  Individual control of (2) the date set forth the than SIX MONTHS from the mailing	fidavit, or other evider compliance with 37 C ust be filed within one in the final rejection, when the final rejection in the final rejection.	nce, which FR 41.31; or (3) of the following ichever is later. In on.				
Examiner Note: If box 1 is checked, check either box (a) or ( TWO MONTHS OF THE FINAL REJECTION. See MPEP 70	06.07(f).						
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of extunder 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b) NOTICE OF APPEAL	tension and the corresponding amount shortened statutory period for reply orig than three months after the mailing da	of the fee. The appropr inally set in the final Offi	iate extension fee ce action; or (2) as				
<ol> <li>The Notice of Appeal was filed on A brief in comp filing the Notice of Appeal (37 CFR 41.37(a)), or any exter a Notice of Appeal has been filed, any reply must be filed</li> </ol>	nsion thereof (37 CFR 41.37(e)), to	avoid dismissal of th	ns of the date of e appeal. Since				
AMENDMENTS	la de la compania de	90 (1)					
<ol> <li>The proposed amendment(s) filed after a final rejection, but prior to the date of filing a brief, will <u>not</u> be entered because</li> <li>(a) They raise new issues that would require further consideration and/or search (see NOTE below);</li> <li>(b) They raise the issue of new matter (see NOTE below);</li> </ol>							
(c) ☐ They are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for appeal; and/or							
(d) They present additional claims without canceling a NOTE: (See 37 CFR 1.116 and 41.33(a)).	corresponding number of finally rej	ected claims.					
4. The amendments are not in compliance with 37 CFR 1.116	21. See attached Notice of Non-Co	mnliant Amendment	(DTOL_324)				
5. Applicant's reply has overcome the following rejection(s):		mpliant Amendment	(FTOL-324).				
<ol> <li>Applicant's reply has overcome the following rejection(s).</li> <li>Newly proposed or amended claim(s) would be allowable if submitted in a separate, timely filed amendment canceling the non-allowable claim(s).</li> </ol>							
7.  For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is provided that the status of the claim(s) is (or will be) as follows: Claim(s) allowed: none. Claim(s) objected to: none. Claim(s) rejected: 1-3,7-9 and 13-41. Claim(s) withdrawn from consideration: 4-6 and 10-12.	□ will not be entered, or b) ☑ wil vided below or appended.	ll be entered and an e	explanation of				
AFFIDAVIT OR OTHER EVIDENCE							
<ol> <li>The affidavit or other evidence filed after a final action, bu because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e).</li> </ol>	t before or on the date of filing a No d sufficient reasons why the affidav	otice of Appeal will <u>no</u> rit or other evidence is	t be entered necessary and				
<ol> <li>The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to o showing a good and sufficient reasons why it is necessary</li> </ol>	vercome all rejections under appea	al and/or appellant fai	Is to provide a				
10. The affidavit or other evidence is entered. An explanation of the status of the claims after entry is below or attached.  REQUEST FOR RECONSIDERATION/OTHER							
<ol> <li>The request for reconsideration has been considered bu See Continuation Sheet.</li> </ol>	t does NOT place the application in	n condition for allowa	nce because:				
12. Note the attached Information Disclosure Statement(s). (	(PTO/SB/08) Paper No(s).	Thail					
		Thành T. Nguyen Examiner Art Unit: 2813					

U.S. Patent and Trademark Office PTOL-303 (Rev. 08-06) Continuation of 11. does NOT place the application in condition for allowance because: Applicant contends that there is motivation in combining Yoon et al. with Wurster et al. is not sufficient. In response to applicant that the motivation for combining the reference in order to growth the oxide layer. Applicant further contends that Wurster teaches forming the oxide on the sidewalls of a capacitor trench which is not part of gate stack. In response to applicant that Yoon et al clearly teach forming the oxide film (18) by oxygen thermal oxidation which is a part of the gate stack. however, Yoon does not clearly teach that the gate oxide film is a wetgate oxide. It is known that wet oxide is formed by wet oxygen oxidation or water oxidation which is evidenced by Wurster. Examiner only relies on the Wurster to show the oxide film can formed by either oxygen or water through the thermal oxidation..